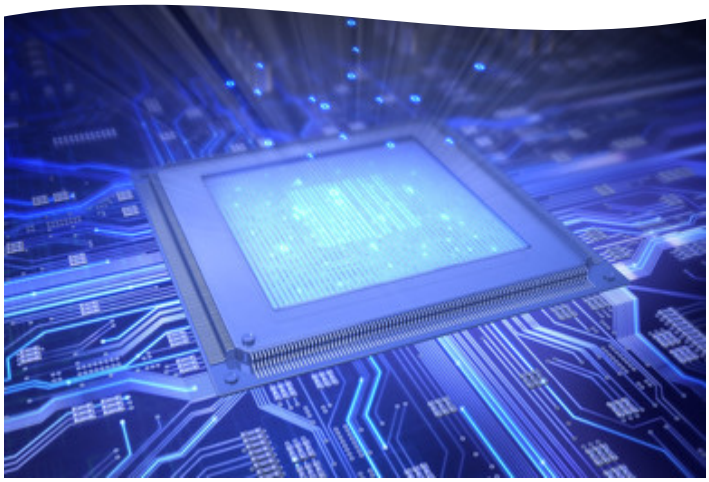
^{11}B in the Form of Boron Trifluoride Gas for Semiconductor Manufacture



Boron trifluoride gas is the ideal silicon wafer dopant for the production of highly integrated, high-density microchips. $^{11}BF_3$ provides for greater efficiency and increased production throughput, and helps to make chips smaller and better.

NUKEM Isotopes GmbH
Rodenbacher Str. 47, 63755 Alzenau, Germany, T: +49 (0)6023 9474-800, F: +49 (0)6023 9474-813
E: info@nukemisotopes.de, I: www.nukem-isotopes.com

^{11}B in the Form of $^{11}BF_3$ Gas

Specification

Physical properties:

- Material — ^{11}B – Boron-11 in the form of Boron Trifluoride Electronic Grade
- Enrichment — ^{11}B > 99,8at%

Chemical Properties:

- Form — BF_3
- Purity — > 99,9vol%

Impurities in vppm

Ar	≤ 25
O_2	≤ 25
CO_2	≤ 25
HF	≤ 25
N_2	≤ 25
SiF_4	≤ 100
SO_2	≤ 25

Our gas is fully compatible with VLIS-requirements.

NUKEM Isotopes GmbH
Rodenbacher Str. 47, 63755 Alzenau, Germany, T: +49 (0)6023 9474-800, F: +49 (0)6023 9474-813
E: info@nukemisotopes.de, I: www.nukem-isotopes.com